

Supporting Information

for

Low-dose patterning of Pt nanoclusters on carbon nanotubes by focused-electron-beam-induced deposition as studied by TEM

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Detailed deposition parameters

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Table S1: Detailed deposition parameters for Figure 4.

	a	b	c	d
Beam voltage	30 kV	30 kV	30 kV	30kV
Beam current	0.2 nA	0.2 nA	0.2 nA	0.2nA
Defocus value	0 μm	4 μm	8 μm	10 μm
pitch	2.5 nm	17.6 nm	35.0 nm	43.7nm
Loop time	168.1 ms	3.3 ms	843 μs	554 μs
passes	2	103	412	638
blur	0 nm	17.5 nm	34.9 nm	43.7nm

Table S2: Detailed deposition parameters for Figure 6.

Beam current = 0.2 nA	Dwell time = 50 ns	Dwell time = 100 ns	Dwell time = 500 ns	Dwell time = 1 μs	Dwell time = 10 μs
Beam voltage = 1 kV, pitch = 19.68nm	$t_{\text{loop}} = 134.6\mu\text{s}$, Passes = 13800	$t_{\text{loop}} = 267.2\mu\text{s}$, Passes = 6908	N/A	$t_{\text{loop}} = 2.7 \text{ ms}$, Passes = 692	$t_{\text{loop}} = 26.5\text{ms}$, Passes = 69
Beam voltage = 3kV, pitch = 8.03nm	$t_{\text{loop}} = 847\mu\text{s}$, Passes = 2385	$t_{\text{loop}} = 1.7\text{ms}$, Passes = 1194	$t_{\text{loop}} = 8.5\text{ms}$, Passes = 239	$t_{\text{loop}} = 16.9\text{ms}$, Passes = 119	$t_{\text{loop}} = 160\text{ms}$, Passes = 12
Beam voltage = 5kV, pitch = 6.22nm	$t_{\text{loop}} = 1.4\text{ms}$, Passes = 1200	$t_{\text{loop}} = 2.7 \text{ ms}$, Passes = 600	$t_{\text{loop}} = 13.5\text{ms}$, Passes = 120	$t_{\text{loop}} = 26.9\text{ms}$, Passes = 60	$t_{\text{loop}} = 269\text{ms}$, Passes = 6
Beam voltage = 10 kV, pitch = 4.4nm	$t_{\text{loop}} = 3\text{ms}$, Passes = 600	$t_{\text{loop}} = 6.1\text{ms}$, Passes = 300	$t_{\text{loop}} = 30.4\text{ms}$, Passes = 60	$t_{\text{loop}} = 60.8\text{ms}$, Passes = 30	$t_{\text{loop}} = 607.6\text{ms}$, Passes = 3
Beam voltage = 15 kV, pitch = 3.6nm	$t_{\text{loop}} = 4.4\text{ms}$, Passes = 450	$t_{\text{loop}} = 7.9\text{ms}$, Passes = 260	$t_{\text{loop}} = 44.5\text{ms}$, Passes = 45	$t_{\text{loop}} = 79\text{ms}$, Passes = 26	$t_{\text{loop}} = 789.6 \text{ ms}$, Passes = 3
Beam voltage = 30 kV, pitch = 2.5nm	$t_{\text{loop}} = 8.4\text{ms}$, Passes = 238	$t_{\text{loop}} = 16.8\text{ms}$, Passes = 120	$t_{\text{loop}} = 84\text{ms}$, Passes = 24	$t_{\text{loop}} = 168.1\text{ms}$, Passes = 12	$t_{\text{loop}} = 2\text{s}$, Passes = 1